



TES detector and array production for the HOLMES experiment

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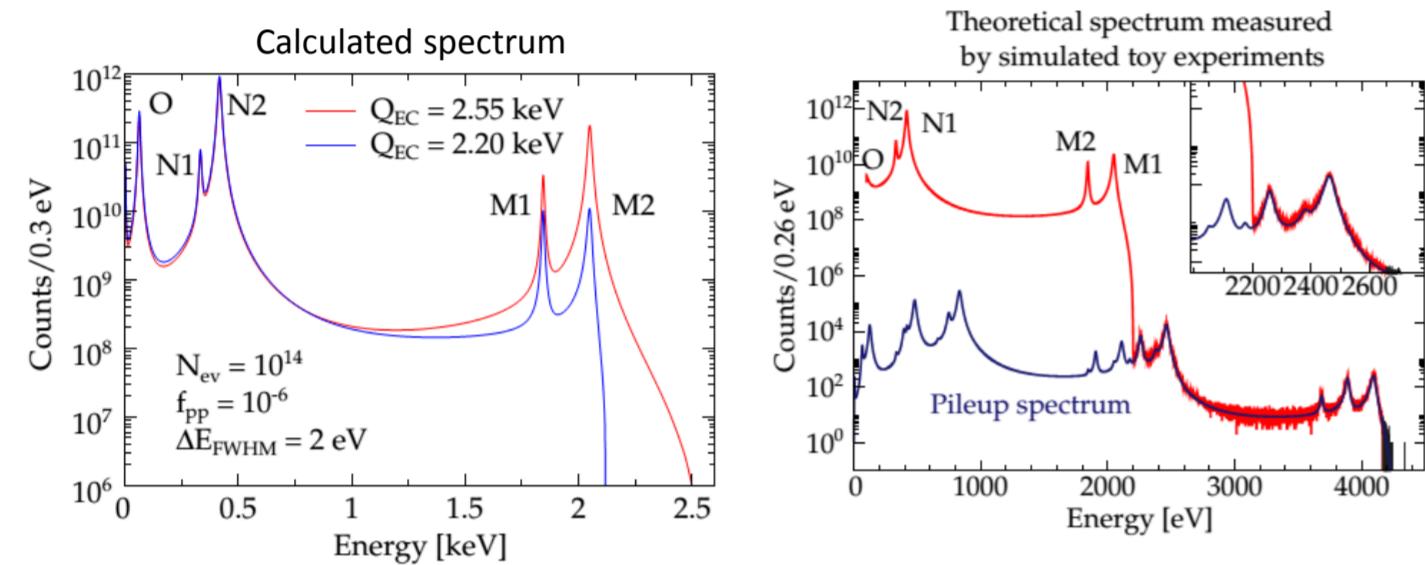
The ^{163}Ho electron capture

FINAL GOAL:
measure the ν_e mass
with sub-eV statistical sensitivity
using the Q-value determination of Ho decay

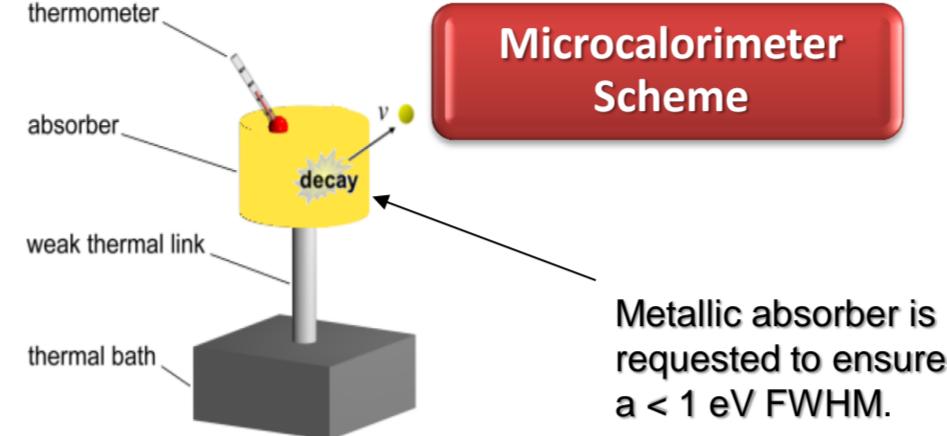


Experiment baseline:

- Transition Edge Sensors (TES) with ^{163}Ho implanted $\text{Bi}: \text{Au}$ absorbers;
- $6.5 * 10^{13}$ nuclei per detector $\Rightarrow 300 \text{ dec/s}$;
- $\Delta E \cong 1 \text{ eV}$ and $\tau_{\text{rise}} \cong 1 \text{ s}$;
- $3 * 10^{13}$ events in 3 years;

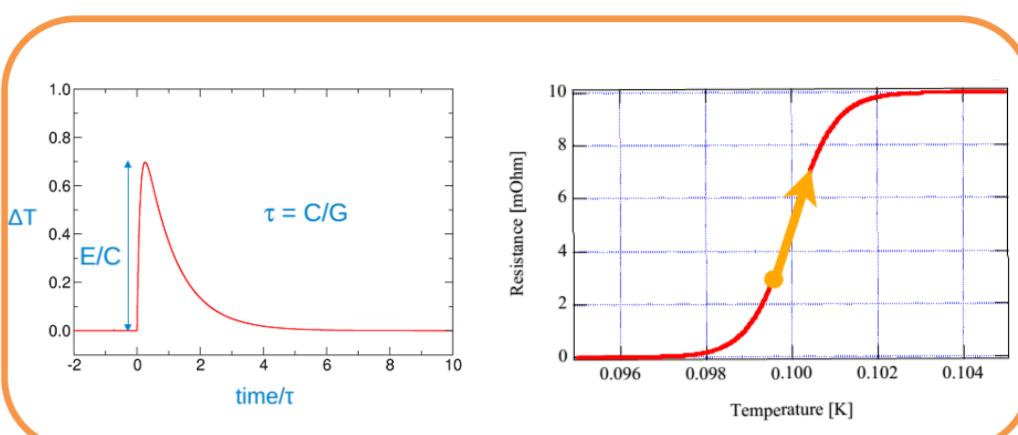


The microcalorimeter and TES detectors



Microcalorimeter Scheme

Metallic absorber is requested to ensure a $< 1 \text{ eV FWHM}$.



Transition Edge Sensors use the resistive transition of a superconductor

Highlights on microcalorimeters:

- The heat equation in a calorimeter:
 $C \frac{d\Delta T}{dt} + G_{\text{eff}} \Delta T = \delta E$
 $\Delta T = \frac{E}{C} e^{-\frac{t}{\tau}}$
- $\tau = \frac{C}{G_{\text{eff}}}$ (if no feedback is considered)
- Energy resolution:
 $\Delta E = (\sqrt{k_b T^2 C})$
- Heat capacity and thermal conductance:
 $C \propto \alpha T^3 + \beta T$

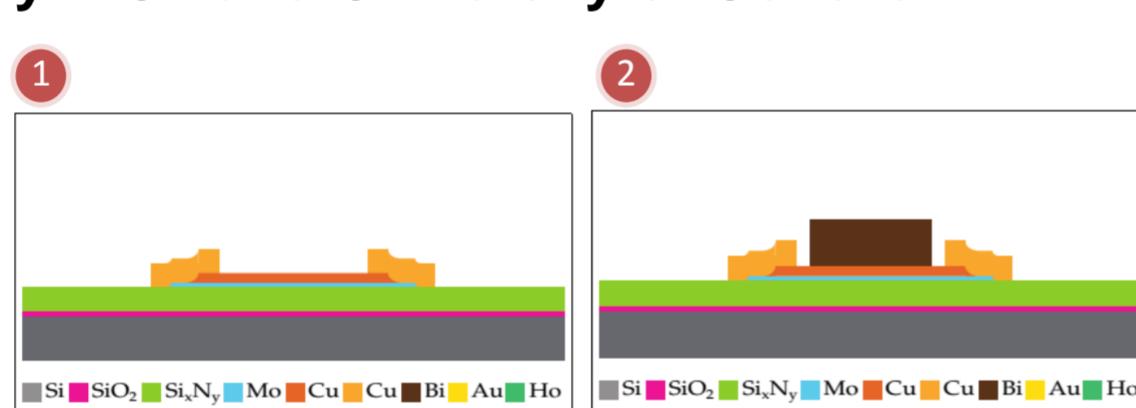
Low temperature and low C are needed.

Detectors microfabrication and array design

Six step TES and Bismuth absorber microfabrication process by NIST and University of Genova

Phase 1 @NIST:

- Mo:Cu proximity TES ($T_c \cong 100 \text{ mK}$);
- SiO_2 stopper layer;
- Si_xN_y membrane for thermal insulation;
- Deposited in a Si substrate;



Phase 2 @NIST:

- Bismuth deposition for the first absorber layer ($2 \div 4 \mu\text{m}$) by lift-off process:
 - Photoresist deposition (sacrificial layer);
 - Target material (Bi) deposition;
 - Wash out of the sacrificial layer;

Phase 3 @NIST:

- Gold deposition for the second absorber layer ($0.1 \div 0.2 \mu\text{m}$);
- Lift off not finished (no photoresist wash out);
- Ship to Genoa (^{163}Ho implantation);

Phase 4 @Genoa:

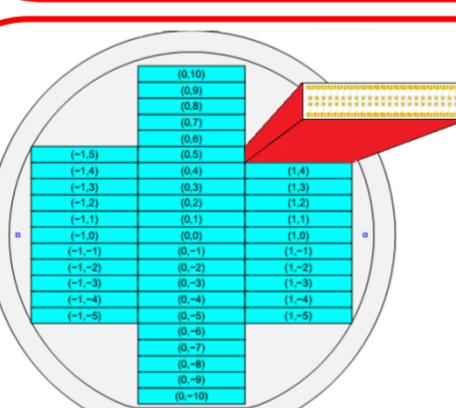
- ^{163}Ho implantation;
- Metallic $^{163}\text{Ho}/\text{Er}/\text{Au}$ anode (source);
- Magnetic mass separation;
- Implantation and magnetic separation;

Phase 5 @Genoa:

- Gold film deposition for full containment:
 - ^{163}Ho coating with thin Au ($0.1 \div 0.2 \mu\text{m}$) layer;

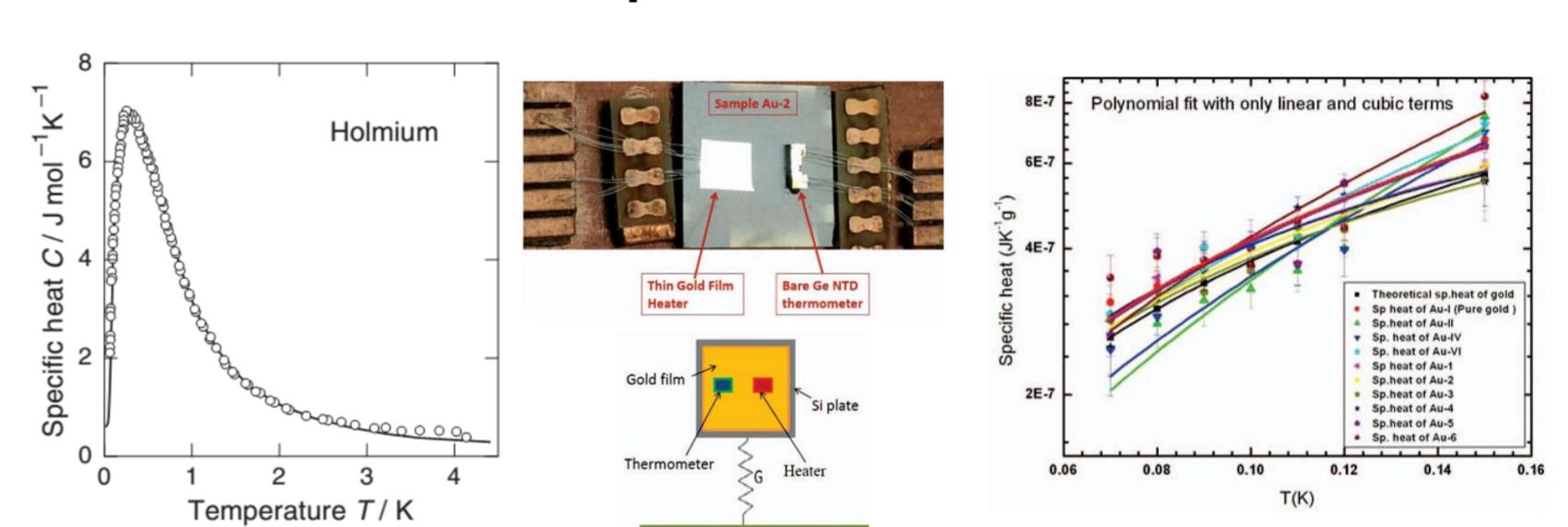
Phase 6 @Genoa:

- Lift off of the Au:Ho:Au layer;
- ^{163}Ho -implanted Au-absorber.



The absorber heat capacity

The specific heat of ^{163}Ho

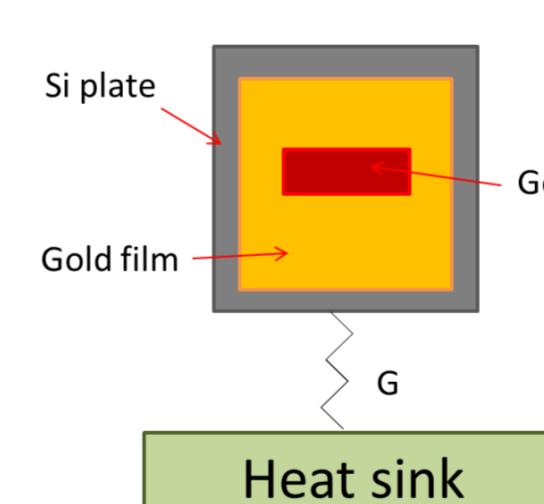


- Because Ho presents $J=7/2$ due to hyperfine level splitting an high concentration in the metallic absorber may cause an excess in the measured total heat capacity .

- Old specific heat measurement setup: a gold foil glued on the sample was used as heater.

- Preliminary C_p measurements on Si:Au implanted samples show no influence from Ho. However more detailed curves of C_p on the same Si/Au implanted samples are needed!

A more precise measurement...



Samples will be heated in 3 ways:

- α source
- Ligh pulse
- Joule heating



$^3\text{He}-^4\text{He}$ dilution cryostat will be used:

- $T=5 \text{ mK}$ can be reached.
- $200 \mu\text{W}$ refrigerating power.

Conclusions

- We need 300 decays/s per sample in order to reach $< 1 \text{ eV}$ neutrino mass statistical sensitivity (see also A.P. Puiu's poster n. 032515);
- We optimized the microfabrication process and the TES array design in order to maximize the number of detectors.
- A dummy 3" wafer with a total of 43 stripes (1978 detectors) has been fabricated by NIST, and should be tested and implanted in Genoa (see G. Pizzigoni's poster n. 032315);
- New C_p measurements on Si:Au implanted samples should be achieved in order to be sure that no excess specific heat arises at $T < 100 \text{ mK}$.